

OXFORD PECVD 418440

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BRIEF DESCRIPTION

Oxford Instruments' PlasmaPro®100 PECVD (Plasma Enhanced Chemical Vapour Deposition) is a versatile instrument that can deposit silicon oxide, silicon nitride, Silicon carbide, amorphous silicon, and other films.

RESEARCH SERVICES

PECVD deposition of Silicon-based thin films on wafers up to 8“.

METHODS & EXPERTISE ON THE RESEARCH INFRASTRUCTURE

Material-Portfolio:

- SiNx
- SiO₂
- SiC
- a-Si

CONTACT

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